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(71) Applicant(s):

FUJIFILM CORPORATION [JP/JP]; 26-30, Nishiazabu 2-chome, Minato-ku, Tokyo 1068620 (JP) *(for all designated states)*

(72) Inventor(s):

KANEKO Yushi; c/o FUJIFILM Corporation, 4000, Kawashiri, Yoshida-cho, Haibara-gun, Shizuoka 4210396 (JP)

TAGUCHI Yoshinori; c/o FUJIFILM Corporation, 4000, Kawashiri, Yoshida-cho, Haibara-gun, Shizuoka 4210396 (JP)

TAKISHITA Hirota; c/o FUJIFILM Corporation, 4000, Kawashiri, Yoshida-cho, Haibara-gun, Shizuoka 4210396 (JP)

(74) Agent(s):

WATANABE Mochitoshi; XYMAX Iwamoto-cho Building 6F., 3-3, Iwamoto-cho 2-chome, Chiyoda-ku, Tokyo 1010032 (JP)

(54) Title (EN): COMPOSITION, FILM, LENS, SOLID STATE IMAGE SENSOR, AND COMPOUND

(54) Title (FR): COMPOSITION, FILM, LENTILLE, ÉLÉMENT D'IMAGERIE À SEMI-CONDUCTEURS, ET COMPOSÉ

(54) Title (JA): 組成物、膜、レンズ、固体撮像素子、化合物

(57) Abstract:

(EN): The present invention provides a composition which is capable of forming a film having a high refractive index and which has excellent conformability to level differences. Moreover, the present invention provides a film obtained using the composition, a lens comprising the film, and a solid state image sensor comprising the film or the lens. The present invention further provides a compound used for the composition. The composition comprises a compound represented by general formula (I) and a solvent, wherein the content of the compound represented by general formula (I) is 30 mass% or more of the total solids in the composition. (A)_m-X-(B)_n (I)

(FR): L'invention fournit une composition qui permet de former un film présentant un indice de réfraction élevé, et qui se révèle excellente en termes d'adaptation aux différences de niveau. L'invention fournit également un film obtenu à l'aide de ladite composition, une lentille contenant ledit film, et un élément d'imagerie à semi-conducteurs contenant ledit film ou ladite lentille. De plus, l'invention fournit un composé mis en œuvre dans ladite composition. La composition de l'invention contient un composé représenté par la formule générale (I) et un solvant, la teneur en composé représenté par la formule générale (I) est supérieure ou égale à 30% en masse de la teneur en matière solide totale contenue dans la composition. (#)#-#-(#)# (#)

(JA): 本発明は、高い屈折率を有する膜を形成できると共に、段差追従性に優れる組成物を提供する。また、本発明は、上記組成物を用いて得られる膜、上記膜を含むレンズ、及び、上記膜又は上記レンズを含む固体撮像素子を提供する。更に、上記組成物に用いられる化合物を提供する。本発明の組成物は、下記一般式(I)で表される化合物及び溶

剤を含む組成物であって、上記一般式(1)で表される化合物の含有量が、組成物中の全固形分に対して、30質量%以上である。(A)_m-X-(B)_n (1)

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